

SHOWERHEAD DESIGN

BACKGROUND OF THE DISCLOSURE

Field of the Disclosure

[0001] Embodiments of the present disclosure generally relate to a showerhead design having a reflector plate with a gas injection insert for radially distributing gas.

Description of the Related Art

[0002] Semiconductor substrates are processed for a wide variety of applications, including the fabrication of integrated devices and microdevices. One method of processing substrates includes depositing oxygen radicals on an upper surface of the substrate. For example, Applied Materials, Inc., of Santa Clara, California, offers a RadOx® process that heats the substrate with lamps and injects hydrogen and oxygen into a processing chamber. The gases form radicals when they strike the surface of the substrate to form a layer on the substrate, e.g., oxygen radicals form a silicon dioxide layer on a silicon substrate.

[0003] Current processing chamber showerheads used for radical oxygen deposition on 300 mm substrates have limited deposition control, resulting in poor processing uniformity. For example, low processing chamber pressure requirements for radial oxygen deposition and current showerhead designs result in gas reaching the substrate at a high velocity. The high velocity of the gas causes impingement on the substrate and prevents the gas from being adequately heated. On the other hand, oxygen radicals generated from combustion quickly recombine to create a short life cycle for the oxygen radicals. Therefore, the limited deposition control due to the high velocity of the gas combined with the short life cycle of oxygen radicals results in greater deposition at the center of the substrate, and poor deposition at the edges of the substrate.

[0004] Therefore, there is a need for an improved showerhead design that provides deposition control for more uniform deposition throughout the substrate, i.e., from the center to the edge.

SUMMARY OF THE DISCLOSURE

[0005] In one embodiment, a shower head assembly is disclosed herein. The showerhead assembly includes a reflector plate and a gas injection insert. The reflector plate has at least one gas injection port disposed therethrough. The gas injection insert is disposed in the reflector plate. The gas injection insert has a plurality of apertures. The gas injection insert includes a baffle plate. The baffle plate is disposed in the gas injection insert. The baffle plate has a plurality of apertures. A first plenum is formed between a first portion of the baffle plate and the reflector plate. A second plenum is formed between a second portion of the baffle plate and the reflector plate. The plurality of apertures of the gas injection insert and the plurality of apertures of the baffle plate are not axially aligned.

[0006] In another embodiment a processing chamber is disclosed herein. The processing chamber includes a substrate support and a showerhead assembly. The substrate support is configured to rotate a substrate during processing. The showerhead assembly is disposed above the substrate support. The showerhead assembly includes a reflector plate and a gas injection insert. The reflector plate has a first gas injection port a second gas injection port disposed therethrough. The gas injection insert is disposed in the reflector plate. The gas injection insert has a plurality of apertures. The gas injection insert includes at least two baffle plates radially disposed in the gas injection insert about a center of the reflector plate. Each baffle plate has a plurality of apertures. A first plenum is formed between a first portion of the baffle plate and the reflector plate. A second plenum is formed between a second portion of the baffle plate and the reflector plate. The first plenum is separated from the second plenum by a wall of the reflector plate. The plurality of apertures of the gas injection insert and the baffle plate are not axially aligned.

[0007] In yet another embodiment, a showerhead assembly is disclosed herein. The showerhead assembly includes a reflector plate and a gas injection insert. The reflector plate has a first injection port and a second gas injection port disposed therethrough to deliver gas to a first plenum and a second plenum. The gas injection insert is disposed in the reflector plate, below the first and second plenums. The gas injection insert includes a plurality of apertures. The number and size of the apertures is selected based on the flow rate of gas flowing through the first and

second gas injection ports. The gas injection insert includes a baffle plate disposed in the gas injection insert. The baffle plate is exposed to the first and second plenums. The baffle plate is configured to reduce the flow of rate of gas flowing through the first and second plenums.

BRIEF DESCRIPTION OF THE DRAWINGS

[0008] So that the manner in which the above recited features of the present disclosure can be understood in detail, a more particular description of the disclosure, briefly summarized above, may be had by reference to embodiments, some of which are illustrated in the appended drawings. It is to be noted, however, that the appended drawings illustrate only typical embodiments of this disclosure and are therefore not to be considered limiting of its scope, for the disclosure may admit to other equally effective embodiments.

[0009] Figure 1 is a schematic view of a processing chamber according to one embodiment of the disclosure.

[0010] Figure 2A illustrates an enlarged view of a showerhead assembly, according to one embodiment of the disclosure.

[0011] Figure 2B illustrates a cross-sectional enlarged view of a baffle plate with a gas injection insert disposed therein, according to one embodiment of the disclosure.

[0012] Figure 3 illustrates an enlarged bottom view of a reflector plate according to one embodiment of the disclosure.

[0013] Figure 4 illustrates an enlarged top view of a gas injection insert according to one embodiment of the disclosure.

[0014] Figure 5 illustrates an enlarged bottom view of a gas injection insert according to one embodiment of the disclosure.

[0015] To facilitate understanding, identical reference numerals have been used, where possible, to designate identical elements that are common to the figures. It is contemplated that elements and features of one embodiment may be beneficially incorporated in other embodiments without further recitation.

DETAILED DESCRIPTION

[0016] Figure 1 illustrates a schematic view of a rapid thermal processing chamber 100 according to one embodiment of the disclosure. Although details of the disclosure are described as utilized within a rapid thermal processing chamber, embodiments described herein may be utilized in other processing systems and devices where uniform deposition is desired, such as other deposition chambers and etch chambers.

[0017] The processing chamber 100 includes a contactless or magnetically levitated substrate support 104 and a chamber body 102. The chamber body 102 has sidewalls 108, a bottom wall 110, and a top wall 112. The sidewalls 108, bottom wall 110, and top wall 112 define an interior volume 121. The top wall 112 includes a lid 116 having a showerhead assembly 127. The sidewalls 108 typically include at least one substrate access port 148. The substrate access port 148 facilitates entry and egress of a substrate 140. The processing chamber 100 may also include a radiant heat source 106 disposed in an inside diameter of the substrate support 104.

[0018] The substrate support 104 is adapted to magnetically levitate and rotate a substrate (not shown) within the interior volume 121. The substrate support 104 includes an annular body 199. The annular body 199 includes a magnetic ring section 130 and a substrate support section 132. The support section 132 extends from an upper surface of the magnetic ring section 130 to support a support ring 134. The support ring 134 facilitates alignment and provides a seating surface for the substrate 140.

[0019] The processing chamber 100 also includes a window 114 made from a material transparent to heat and light of various wavelengths. The various wavelengths may include light in the infra-red (IR) spectrum, through which photons from a radiant heat source 106 may heat the substrate 140. The window 114 may also include a plurality of lift pins 144. The lift pins 144 are adapted to selectively contact and support the substrate 140 to facilitate transfer of the substrate 140 into and out of the processing chamber 100.

[0020] In one embodiment, the radiant heat source 106 includes a lamp assembly formed from a housing. The housing includes a plurality of honeycomb

tubes 160 in a coolant assembly 161. The honeycomb tubes 160 are coupled to a coolant source 183.

[0021] An atmosphere control system 164 is also coupled to the interior volume 121 of the chamber body 102. The atmosphere control system 164 generally includes throttle valves and vacuum pumps for controlling chamber pressure.

[0022] The showerhead assembly 127 is configured to deliver one or more gases to the substrate 140. The showerhead assembly 127 includes a reflector plate 118 disposed below the lid 116. The reflector plate 118 faces the substrate support 104. The reflector plate 118 is configured to reflect IR light that is radiating off the substrate 140 back onto the substrate 140. A cooling plate 115 may optionally be disposed around and circumscribe the reflector plate 118 to cool the reflector plate 118.

[0023] In one embodiment, the showerhead assembly 127 includes at least a first gas injection port 138 and a second gas injection port 128 formed through the lid 116 and the reflector plate 118. An enlarged schematic view of the first gas injection port 138 and the second gas injection port 128 of the showerhead assembly 127 may be seen in Figure 2A. The first gas injection port 138 is configured to inject gas from a first gas source 123 to a first plenum 129 in a generally radially inward direction. The second gas injection port 128 is configured to inject gas from a second gas source 125 to a second plenum 120 in a generally radially inward direction. The first and second plenums 129, 120 are formed in the reflector plate 118. The first plenum 129 is exposed to the first gas injection port 138. The second plenum 120 is exposed to the second gas injection port 128.

[0024] In one embodiment, the first gas injection port 138 (for providing gas to the first plenum 129) is located in the second quarter of the reflector plate 118. For example, the first gas injection port 138 is located between about 30 mm to about 40 mm from the center of the reflector plate 118. In one embodiment, the second gas injection port 128 (for providing gas to the second plenum 120) is located in the first quarter of the reflector plate 118. For example, the second gas injection port 128 is located between about 112 mm to about 122 mm from the center of the reflector plate 118. In one embodiment, the first and second gas injection ports 138, 128

each have a diameter of between about 1 mm and about 10 mm, for example, about 5 mm or about 5.1 mm.

[0025] In one embodiment, the first gas source 123 supplies oxygen gas (O_2) and the second gas source 125 supplies hydrogen gas (H_2). An oxygen and hydrogen gas mixture (O_2/H_2) is thus supplied to the first and second plenums 129, 120. In one embodiment, the gas mixture is between about 23 percent to about 43 percent hydrogen gas, and between about 57 percent to about 77 percent oxygen gas, for example, about 33 percent hydrogen gas and about 67 percent oxygen gas. The gas mixture flowing through the first plenum 129 forms an inner zone 171 in the showerhead assembly 127. The gas mixture flowing through the second plenum 120 forms an outer zone 172 in the showerhead assembly 127. The separate and distinct inner and outer zones 171, 172 in the showerhead assembly 127 advantageously allow the gas mixture to be controlled and tuned prior to being deposited on the substrate 140, depending on the processing requirements.

[0026] The reflector plate 118 also includes one or more gas injection inserts 124 disposed in the reflector plate 118. Figure 3 illustrates an enlarged bottom view of the reflector plate 118. In one embodiment, the reflector plate 118 includes one gas injection insert 124, two gas injection inserts 124, each located about every 180 degrees around the reflector plate 118 (as shown in Figure 1), or four gas injection inserts 124, located about every 90 degrees around the reflector plate 118 (as shown in Figure 3). The baffle plate 122 is coupled to the reflector plate 118 by a plurality of screws 290. The plurality of screws are configured to fit within a plurality of screw holes 292 formed in the reflector plate 118 and a plurality of screw holes 294 formed in the baffle plate 122.

[0027] Figure 2B illustrates a cross-sectional view of a portion of the baffle plate 122 and the gas injection insert 124. The baffle plate 122 is shown coupled to an inner edge 202 of the gas injection insert 124. For example, in one embodiment, the baffle plate 122 may be welded to the inner edge 202 of the gas injection insert 124. The baffle plate 122 is suspended in the gas injection insert 124 such that the third plenum 131 is formed between the baffle plate 122 and the gas injection insert 124. The apertures 117 in the baffle plate 122 are shown to be not axially aligned with the apertures 126 formed in the gas injection insert 124 such that a tortuous flow

path is formed from the first and second plenums (not shown) to the third plenum 131. Figure 4 illustrates an enlarged top view of the gas injection insert 124. The gas injection insert 124 has a generally oblong shaped body. The gas injection insert 124 includes an oblong shaped baffle plate 122 disposed in the body of the gas injection insert 124. The gas injection insert 124 includes a plurality of apertures 126 (shown in phantom in Figure 4). The gas injection insert 124 is configured to deliver the gas mixture from the first and second plenums 129, 120 through the apertures 126 into the interior volume 121 and to the substrate 140. The baffle plate 122 includes a plurality of apertures 117 formed therethrough. The baffle plate 122 is configured to deaden or slow the flow rate of the gas mixture flowing from the first and second plenums 129, 120 through the apertures 117 and evenly distribute the gas mixture to a third plenum 131 defined by the baffle plate 122 and the injection insert 124. Beneficially, the baffle plate 122 also reduces the overall gas mixture consumption by about 30 percent. Experimental results indicate that the velocity of the gas mixture may be reduced by about 98 percent. For example, the velocity of the gas mixture may be reduced from about 100 m/s (using a conventional showerhead design) to about 10 m/s (using the above described baffle plate 122) towards the substrate 140.

[0028] In one embodiment, the number of apertures 117 in the baffle plate 122 is between about 20 and about 30 apertures 117, for example, about 24 or about 25 apertures 117. In one embodiment, the apertures 117 are formed in a single column in the baffle plate 122. In one embodiment, the radius of the apertures 117 is between about 0.25 mm and about 1.52 mm, for example, about 0.793 mm. In one embodiment, the number of apertures 126 in the gas injection insert 124 is greater than the number of apertures 117 in the baffle plate 122.

[0029] In one embodiment, the apertures 126 in the gas injection insert 124 are formed in two columns. Each column may have between about 40 and about 60 apertures, for example, about 40 apertures or about 50 apertures, i.e., about 100 apertures. Therefore, in one embodiment, there are about 100 apertures 126 (50 apertures x two columns). In one embodiment, the apertures 117 and the apertures 126 are offset to create a tortuous flow path through the showerhead assembly 127. In one embodiment, the radius of the apertures 126 is between about 0.25 mm and

about 1.52 mm, for example, about 0.79 mm. In another embodiment, (i) the number and size of the apertures 126; (ii) the number of columns having the apertures 126; and (iii) the thickness of the gas injection insert 124 itself, may be selected based on the flow rate of the gas mixture flowing from the first and second plenums 129, 120 (i.e., the inner zone 171 and the outer zone 172) to the third plenum 131, and finally flowing radially towards the substrate 140.

[0030] Figure 5 is an enlarged bottom view of a gas injection insert 500 having a plurality of apertures 126 varying in size. In one embodiment, the apertures 126 of the gas injection insert 500 vary in size to form a gas flow gradient. For example, the apertures 126 may have a larger surface area on one end of the gas injection insert 500 than an opposing end of the gas injection insert 500. In one embodiment, the apertures 126 are formed in two columns. Each column has about 50 apertures 126 (as shown in Figure 5). The apertures 126 in each column increase gradually in size from a first end 502 of the gas injection insert 500 to an opposing second end 504 of the gas injection insert 500. In one embodiment, the apertures 126 increase from a radius of between about 0.34 mm to about 1.98 mm, for example, a radius of between about 0.44 mm to about 0.98 mm.

[0031] Referring to Figures 1 and 5, the gas injection insert 500 is disposed in the reflector plate 118, such that each column of about apertures 126, e.g., two columns having about 50 apertures 126 each, spans the length of both the first and second plenums 129, 120. As such, about a first half of the apertures 126 in each column, i.e., about 25 apertures 126, span the length of the first plenum 129 as part of the inner zone 171. The second half of the apertures 126 in each column, i.e., about 25 apertures 126, span the length of the second plenum 120 as part of the outer zone 172.

[0032] In one embodiment of operation, where deposition of the gas mixture may be higher at the center of the substrate 140 than the edges of the substrate 140, two separate volumetric flow rates of the gas mixture may be provided to the first and second gas injection ports 138, 128. For example, in one embodiment the overall gas mixture is provided at about 2 slm or about 5 slm through the showerhead assembly 127.

[0033] In one embodiment, the gas mixture flowing through the first plenum 129 has a slower flow rate than the gas mixture flowing through the second plenum 120 in order to reduce the center-high deposition on the substrate 140. For example, the gas mixture is provided through the first gas injection port 138 and into the first plenum 129 at about 0.69 slm or about 1.71 slm (i.e., the inner zone 171). The gas mixture is then provided through the second gas injection port 128 and into the second plenum 120 at about 1.31 slm or about 3.29 slm (i.e., the outer zone 172). Because the first plenum 129 is disposed closer to the center of the substrate 140 than the second plenum 120, the first end 502 of the gas injection insert 500 (having the smaller aperture 126 size) is disposed below the first plenum 129 to account for the center-high deposition on the substrate 140. Conversely, because the second plenum 120 is disposed closer to the edge of the substrate 140 than the first plenum 129, the second end 504 of the gas injection insert 500 (having the larger aperture 126 size) is disposed below the second plenum 120. As such, the overall gas mixture flow rate through the showerhead assembly 127 can advantageously be individually controlled and tuned through the above disclosed inner and outer zones 171, 172 to create an even gas mixture flow rate between the center and the edges of the substrate 140 and therefore promote overall uniform deposition over the substrate 140.

While the foregoing is directed to embodiments of the present disclosure, other and further embodiments of the disclosure may be devised without departing from the basic scope thereof, and the scope thereof is determined by the claims that follow.

IN THE CLAIMS:

1. A showerhead assembly comprising:
 - a reflector plate having at least one gas injection port disposed therethrough;
 - and
 - a gas injection insert disposed in the reflector plate and having a plurality of apertures, wherein the gas injection insert comprises:
 - a baffle plate disposed in the gas injection insert and having a plurality of apertures, wherein a first plenum is formed between a first portion of the baffle plate and the reflector plate, wherein a second plenum is formed between a second portion of the baffle plate and the reflector plate, and wherein the plurality of apertures of the gas injection insert and the plurality of apertures of the baffle plate are not axially aligned.
2. A showerhead assembly comprising:
 - a reflector plate having a first gas injection port and a second gas injection port disposed therethrough to deliver gas to a first plenum and a second plenum;
 - and
 - a gas injection insert disposed in the reflector plate, disposed below the first and second plenums, wherein the gas injection insert includes a plurality of apertures, and wherein the number and size of the apertures is selected based on the flow rate of gas flowing through the first and second gas injection ports, wherein the gas injection insert comprises:
 - a baffle plate disposed in the gas injection insert and exposed to the first and second plenums, wherein the baffle plate is configured to reduce the flow rate of gas flowing through the first and second plenums.
3. The showerhead assembly according to claims 1 or 2, wherein the reflector plate further comprises:
 - a second gas injection port disposed therethrough, the second gas injection port separated from the first gas injection port by a wall of the reflector plate.

4. The showerhead assembly according to claims 1 or 2, wherein the first plenum is concentric to the second plenum.
5. The showerhead assembly according to claims 1 or 2, wherein the showerhead assembly further comprises:
 - a third plenum formed between the baffle plate and the gas injection insert.
6. The showerhead assembly according to claims 5, wherein the third plenum is in fluid communication with the first and second plenums, through the apertures formed through the baffle plate.
7. The showerhead assembly according to claims 6, wherein the plurality of apertures of the gas injection insert are aligned in one or more columns.
8. The showerhead assembly of claim 7, wherein the apertures of the gas injection insert increase in diameter from a first end of the gas injection insert to a second end of the gas injection insert.
9. The showerhead assembly according to claims 1 or 2, wherein the plurality of apertures in the gas injection insert are greater in number than the plurality of apertures in the baffle plate.
10. A processing chamber comprising:
 - a substrate support configured to rotate a substrate during processing; and
 - a showerhead assembly disposed above the substrate support, wherein the showerhead assembly comprises:
 - a reflector plate having a first gas injection port and a second gas injection port disposed therethrough; and
 - a gas injection insert disposed in the reflector plate and having a plurality of apertures, wherein the gas injection insert comprises:
 - at least two baffle plates radially disposed in the gas injection insert about a center of the reflector plate, each baffle plate having a

plurality of apertures, wherein a first plenum is formed between a first portion of the baffle plate and the reflector plate, wherein a second plenum is formed between a second portion of the baffle plate and the reflector plate, the first plenum separated from the second plenum by a wall of the reflector plate, and wherein the plurality of apertures of the gas injection insert and the baffle plate are not axially aligned.

11. The processing chamber of claim 10, wherein the first plenum is concentric to the second plenum.

12. The processing chamber of claim 10, wherein the showerhead further comprises:

a third plenum formed between the baffle plate and the gas injection insert.

13. The processing chamber of claim 12, wherein the third plenum is in fluid communication with the first and second plenums through the apertures formed through the baffle plate.

14. The processing chamber of claim 13, wherein the plurality of apertures of the gas injection insert are aligned in one or more columns.

15. The processing chamber of claim 14, wherein the plurality of apertures of the gas injection insert increase in diameter from a first end of the gas injection insert to a second end of the gas injection insert.